KAI-1010 <u>Kaiser (* 1910)</u>

CCD Image Sensor CCD Image Sensor

Description

The KAI−1010 Image Sensor is a high-resolution monochrome charge coupled device (CCD) device whose non-interlaced architecture makes it ideally suited for video, electronic still and motion/still camera applications. The device is built using an advanced true two-phase, double-polysilicon, NMOS CCD technology. The p+npn− photodetector elements eliminate image lag and reduce image smear while providing antiblooming protection and electronic-exposure control. The total chip size is 10.15 (H) mm \times 10.00 (V) mm

Table 1. GENERAL SPECIFICATIONS

NOTE: All Parameters are specified at $T = 40^{\circ}$ C unless otherwise noted.

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Figure 1. KAI−1010 Interline CCD Image Sensor

Features

- Front Illuminated Interline Architecture
- Progressive Scan (Non-Interlaced)
- Electronic Shutter
- On-Chip Dark Reference
- Low Dark Current
- High Sensitivity Output Structure
- Anti-Blooming Protection
- Negligible Lag
- Low Smear (0.1% with Microlens)

Application

• Machine Vision

ORDERING INFORMATION

See detailed ordering and shipping information on page 2 of this data sheet.

ORDERING INFORMATION

Table 2. ORDERING INFORMATION − KAI−1010 Image Sensor

See the ON Semiconductor *Device Nomenclature* document (TND310/D) for a full description of the naming convention used for image sensors. For reference documentation, including information on evaluation kits, please visit our web site at [www.onsemi.com.](http://onsemi.com)

DEVICE DESCRIPTION

Architecture

Figure 2. Functional Block Diagram

The KAI–1010 consists of 1024×1024 photodiodes, 1024 vertical (parallel) CCD shift registers (VCCDs), and dual 1032 pixel horizontal (serial) CCD shift registers (HCCDs) with independent output structures. The device can be operated in either single or dual line mode. The advanced, progressive-scan architecture of the device allows the entire image area to be read out in a single scan. The active pixels are arranged in a 1008 (H) \times 1018 (V) array with an additional 16 columns and 6 rows of light-shielded dark reference pixels.

Image Acquisition

An electronic representation of an image is formed when incident photons falling on the sensor plane create electron-hole pairs within the individual silicon photodiodes. These photoelectrons are collected locally by the formation of potential wells at each photosite. Below photodiode saturation, the number of photoelectrons collected at each pixel is linearly dependent on light level and exposure time and non-linearly dependent on wavelength. When the photodiode's charge capacity is reached, excess electrons are discharged into the substrate to prevent blooming.

Charge Transport

The accumulated or integrated charge from each photodiode is transported to the output by a three step process. The charge is first transported from the photodiodes to the VCCDs by applying a large positive voltage to the phase-one vertical clock $(\phi V1)$. This reads out every row, or line, of photodiodes into the VCCDs.

The charge is then transported from the VCCDs to the HCCDs line by line. Finally, the HCCDs transport these rows of charge packets to the output structures pixel by pixel. On each falling edge of the horizontal clock, ϕ H2, these charge packets are dumped over the output gate (OG, Figure [4](#page-3-0)) onto the floating diffusion (FDA and FDB, Figure [4](#page-3-0)).

Both the horizontal and vertical shift registers use traditional two-phase complementary clocking for charge transport. Transfer to the HCCDs begins when ϕ V2 is clocked high and then low (while holding $\phi H1A$ high) causing charge to be transferred from ϕ V1 to ϕ V2 and subsequently into the A HCCD. The A register can now be read out in single line mode. If it is desired to operate the device in a dual line readout mode for higher frame rates, this

line is transferred into the B HCCD by clocking ϕ H1A to a low state, and $\phi H1B$ to a high state while holding $\phi H2$ low. After ϕ H1A is returned to a high state, the next line can be transferred into the A HCCD. After this clocking sequence, both HCCDs are read out in parallel.

The charge capacity of the horizontal CCDs is slightly more than twice that of the vertical CCDs. This feature

allows the user to perform two-to-one line aggregation in the charge domain during V-to-H transfer. This device is also equipped with a fast dump feature that allows the user to selectively dump complete lines (or rows) of pixels at a time. This dump, or line clear, is also accomplished during the V-to-H transfer time by clocking the fast dump gate.

Direction of Transfer

Output Structure

Charge packets contained in the horizontal register are dumped pixel by pixel, onto the floating diffusion output node whose potential varies linearly with the quantity of charge in each packet. The amount of potential change is determined by the expression $\Delta V_{FD} = \Delta Q / C_{FD}$. A three stage source-follower amplifier is used to buffer this signal voltage off chip with slightly less than unity gain. The translation from the charge domain to the voltage domain is quantified by the output sensitivity or charge to voltage conversion in terms of μ V/e[−]. After the signal has been sampled off-chip, the reset clock (ϕR) removes the charge from the floating diffusion and resets its potential to the reset-drain voltage (VRD).

Electronic Shutter

The KAI−1010 provides a structure for the prevention of blooming which may be used to realize a variable exposure time as well as performing the anti-blooming function. The anti-blooming function limits the charge capacity of the photodiode by draining excess electrons vertically into the substrate (hence the name Vertical Overflow Drain or VOD). This function is controlled by applying a large potential to the device substrate (device terminal SUB). If a sufficiently large voltage pulse (VES \approx 40 V) is applied to the substrate, all photodiodes will be emptied of charge through the substrate, beginning the integration period.

After returning the substrate voltage to the nominal value, charge can accumulate in the diodes and the charge packet is subsequently readout onto the VCCD at the next occurrence of the high level on ϕ V1. The integration time is then the time between the falling edges of the substrate shutter pulse and ϕ V1. This scheme allows electronic variation of the exposure time by a variation in the clock timing while maintaining a standard video frame rate.

Application of the large shutter pulse must be avoided during the horizontal register readout or an image artifact will appear due to feed ϕ through. The shutter pulse VES must be "hidden" in the horizontal retrace interval. The integration time is changed by skipping the shutter pulse from one horizontal retrace interval to another.

The smear specification is not met under electronic shutter operation. Under constant light intensity and spot size, if the electronic exposure time is decreased, the smear signal will remain the same while the image signal will decrease linearly with exposure. Smear is quoted as a percentage of the image signal and so the percent smear will increase by the same factor that the integration time has decreased. This effect is basic to interline devices.

Extremely bright light can potentially harm solid state imagers such as Charge-Coupled Devices (CCDs). Refer to Application Note *Using Interline CCD Image Sensors in High Intensity Visible Lighting Conditions*.

Physical Description

Pin Description and Device Orientation

Table 3. PIN DESCRIPTION

1. All GND pins should be connected to WELL (P-Well).

2. Pins 2 and 24 must be connected together − only 1 Phase 1 clock driver is required.

3. Pins 3 and 23 must be connected together − only 1 Phase 2 clock driver is required.

IMAGING PERFORMANCE

All the following values were derived using nominal operating conditions using the recommended timing. Unless otherwise stated, readout time $= 140$ ms, integration time $=$ 140 ms and sensor temperature $= 40^{\circ}$ C. Correlated double sampling of the output is assumed and recommended. Many

units are expressed in electrons, to convert to voltage, multiply by the amplifier sensitivity.

Defects are excluded from the following tests and the signal output is referenced to the dark pixels at the end of each line unless otherwise specified.

1. For $\lambda = 550$ nm wavelength, and $V_{\text{SAT}} = 350$ mV.

2. Refer to typical values from Figure 6.
3. Under uniform illumination with outpu

Under uniform illumination with output signal equal to 280 mV.

4. Units: % Peak to Peak. A 200 by 200 sub ROI is used.

Monochrome with Microlens Quantum Efficiency

Figure 6. Nominal KAI−1010−ABA Spectral Response

Angular Quantum Efficiency

Notes:

1. For the curve marked "Horizontal", the incident light angle is varied in a plane parallel to the HCCD.

2. For the curve marked "Vertical", the incident light angle is varied in a plane parallel to the VCCD.

Figure 7. Angular Dependance of Quantum Efficiency

Frame Rates

KAI−1010 Frame Rate vs. Horizontal Clock Frequency

CCD Image Specifications

Table 5. CCD IMAGE SPECIFICATIONS

1. V_{SAT} is the green pixel mean value at saturation as measured at the output of the device with $X_{AB} = 1$. V_{SAT} can be varied by adjusting V_{SUB} .

2. Measured at sensor output.

3. With stray output load capacitance of $C_L = 10$ pF between the output and AC ground.

4. Using maximum CCD frequency and/or minimum CCD transfer times may compromise performance.

5. This is the first field decay lag measured by strobe illuminating the device at (H_{SAT}, V_{SAT}), and by then measuring the subsequent frame's average pixel output in the dark.

6. $\ X_{\sf AB}$ represents the increase above the saturation-irradiance level (H_{SAT}) that the device can be exposed to before blooming of the vertical shift register will occur. It should also be noted that V_{OUT} rises above V_{SAT} for irradiance levels above H_{SAT}, as shown in Figure [9](#page-10-0).

7. Measured under 10% (~ 100 lines) image height illumination with white light source and without electronic shutter operation and below V_{SAT}.

8. It should be noted that there is tradeoff between X_{AB} and V_{SAT} .

Output Amplifier \mathcal{Q} V_{DD} = 15 V, V_{SS} = 0.0 V

Table 6. OUTPUT AMPLIFIER IMAGE SPECIFICATIONS

1. Measured at sensor output with constant current load of $I_{\text{OUT}} = 5$ mA per output.

2. Measured with VRD = 9 V during the floating-diffusion reset interval, (ϕ R high), at the sensor output terminals.

3. Both channels.

4. With stray output load capacitance of $C_L = 10$ pF between the output and AC ground.

General

Table 7. GENERAL IMAGE SPECIFICATIONS

1. Includes amplifier noise and dark current shot noise at data rates of 10 MHz. The number is based on the full bandwidth of the amplifier. It can be reduced when a low pass filter is used.

2. Uses 20LOG (V_{SAT} / V_{N-TOTAL}) where V_{SAT} refers to the output saturation signal.

1. As V_{SUB} is decreased, V_{SAT} increases and anti-blooming protection decreases.

2. As V_{SUB} is increased, V_{SAT} decreases and anti-blooming protection increases.

Figure 10. Example of V_{SAT} vs. V_{SUB}

DEFECT DEFINITIONS

All values are derived under normal operating conditions at 40°C operating temperature.

Table 8. DEFECT DEFINITIONS

1. Sections are 252 (H) \times 255 (V) pixel groups, which divide the imager into sixteen equal areas as shown below.

Figure 11.

Table 9.

OPERATION

Table 10. ABSOLUTE MAXIMUM RATINGS

Stresses exceeding those listed in the Maximum Ratings table may damage the device. If any of these limits are exceeded, device functionality should not be assumed, damage may occur and reliability may be affected.

1. Under normal operating conditions the substrate voltage should be above +7 V, but may be pulsed to 40 V for electronic shuttering.

2. Care must be taken in handling so as not to create static discharge which may permanently damage the device.

3. Per Output. I_{OUT} affects the band-width of the outputs.

4. ϕ R should never be more positive than V_{SUB} .

5. The tolerance on all relative humidity values is provided due to limitations in measurement instrument accuracy.

6. The image sensor shall continue to function but not necessarily meet the specifications of this document while operating at the specified conditions.

7. Refer to Application Note *Using Interline CCD Image Sensors in High Intensity Visible Lighting Conditions*.

Table 11. DC OPERATING CONDITIONS

1. The WELL and GND pins should be connected to P-Well ground.

2. The voltage level specified will disable the fast dump feature.

3. This pin may be pulsed to V_{ES} = 40 V for electronic shuttering
4. Electrical injection test pins. Connect to VDD power supply.

5. Per output. Note also that I_{OUT} affects the bandwidth of the outputs.

6. Pins shown with impedances greater than 1.2 M Ω are expected resistances. These pins are only verified to 1.2 M Ω .

7. The operating levels are for room temperature operation. Operation at other temperatures may or may not require adjustments of these voltages.

8. Refer to Application Note *Using Interline CCD Image Sensors in High Intensity Visible Lighting Conditions*.

Figure 12. Recommended Output Structure Load Diagram

Table 12. AC CLOCK LEVEL CONDITIONS

1. The AC and DC operating levels are for room temperature operation. Operation at other temperatures may or may not require adjustments of these voltages.

2. Pins shown with impedances greater than 1.2 M Ω are expected resistances. These pins are only verified to 1.2 M Ω .

3. When not used, refer to DC operating condition.

4. For single register mode, set ϕ H1B to -7.0 V at all times rather than clocking it.

5. This device is suitable for a wide range of applications requiring a variety of different operating conditions. Consult ON Semiconductor in those situations in which operating conditions meet or exceed minimum or maximum levels.

Table 13. AC TIMING REQUIREMENTS FOR 20 MHZ OPERATION

1. Integration time varies with shutter speed. It is to be noted that smear increases when integration time decreases below readout time (frame time). Photodiode dark current increases when integration time increases, while CCD dark current increases with readout time (frame time).

2. Anti-blooming function is off during photodiode to VCCD transfer.

TIMING

Frame Timing − Single Register Readout

NOTE: When no electronic shutter is used, the integration time is equal to the frame time.

Line Timing − Single Register Readout

Figure 14. Frame Timing − Single Resistor Readout

Figure 15. Pixel Timing − Single Resistor Readout

Electronic Shutter Timing − Single Register Readout

Figure 16. Electronic Shutter Timing − Single Register Readout

Frame Timing − Dual Register Readout

NOTE: When no electronic shutter is used, the integration time is equal to the frame time.

Line Timing − Dual Register Readout

Figure 19. Pixel Timing − Dual Resistor Readout

Fast Dump Timing − Removing Four Lines

Binning − Two to One Line Binning

Timing − Sample Video Waveform

STORAGE AND HANDLING

Table 14. CLIMATIC REQUIREMENTS

1. The image sensor shall meet the specifications of this document while operating at these conditions.

2. The tolerance on all relative humidity values is provided due to limitations in measurement instrument accuracy.

3. The image sensor shall meet the specifications of this document after storage for 15 days at the specified condition.

For information on ESD and cover glass care and cleanliness, please download the *Image Sensor Handling and Best Practices* Application Note (AN52561/D) from [www.onsemi.com.](http://onsemi.com)

For information on environmental exposure, please download the *Using Interline CCD Image Sensors in High Intensity Lighting Conditions* Application Note (AND9183/D) from [www.onsemi.com](http://onsemi.com).

For information on soldering recommendations, please download the Soldering and Mounting Techniques Reference Manual (SOLDERRM/D) from [www.onsemi.com.](http://onsemi.com)

For quality and reliability information, please download the *Quality & Reliability* Handbook (HBD851/D) from [www.onsemi.com.](http://onsemi.com)

For information on device numbering and ordering codes, please download the *Device Nomenclature* technical note (TND310/D) from [www.onsemi.com](http://onsemi.com).

For information on Standard terms and Conditions of Sale, please download [Terms and Conditions](http://www.onsemi.com/site/pdf/ONSEMI_T&C.pdf) from [www.onsemi.com.](http://onsemi.com)

MECHANICAL INFORMATION

Completed Assembly

Note: Cover Glass is manually placed and visually aligned over die – location accuracy is not guaranteed.

Figure 23. Completed Assembly (1 of 2)

Notes:

1. Center of image area is offset from center of package by (−0.02, −0.06) mm nominal.

2. Die is aligned within ± 2 degree of any package cavity edge.

Figure 24. Completed Assembly (2 of 2)

Cover Glass

Notes:

- 1. DUST/SCRATCH COUNT 20 MICRON MAX. (ZONE−A)
- 2. EPOXY: NCO−110SZ
- THICKNESS: 0.002–0.007″ 3. GLASS: SCHOTT D263 eco or equivalent
- 4. DOUBLE−SIDED AR COATING REFLECTANCE
	- a. 420–435 nm < 2.0 %
	- b. 435–630 nm < 0.8 %
	- c. 630–680 nm < 2.0 %

Figure 25. Glass Drawing

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